	Application No.	Applicant(s)
Notice of Allowability	09/761,753	ISHIDA ET AL.
	Examiner	Art Unit
	Fernando L. Toledo	2823
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to the amendment proposed at the June 21, 2004 interview.		
2. The allowed claim(s) is/are <u>1,3-6,8,9 and 22-38</u> .		
3. The drawings filed on 18 January 2001 are accepted by the Examiner.		
 4. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some* c) None of the: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No. 09/041,674. 3. Copies of the certified copies of the priority documents have been received in this national stage application from the International Bureau (PCT Rule 17.2(a)). * Certified copies not received: Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 		
5. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
 6. CORRECTED DRAWINGS (as "replacement sheets") must be submitted. (a) including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached 1) hereto or 2) to Paper No./Mail Date (b) including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d). 7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL. 		
Attachment(s) 1. □ Notice of References Cited (PTO-892)	5.	atent Application (PTO-152)
 Notice of Draftperson's Patent Drawing Review (PTO-948) Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 	Paper No./Mail Dat	 6. ☑ Interview Summary (PTO-413), Paper No./Mail Date <u>20040714</u>. 7. ☑ Examiner's Amendment/Comment
 Examiner's Comment Regarding Requirement for Deposit of Biological Material 	8. ☐ Examiner's Stateme 9. ☐ Other	ent of Reasons for Allowance

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EXAMINER'S AMENDMENT

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Steve Adrian0 on 14 July 2004.

The application has been amended as follows:

In the claims:

Claim 1: (Currently Amended) A process for fabricating a thin-film device, said process comprising:

forming a conducting layer composed of an anodically oxidizable metal on a substrate;

etching said conducting layer to form a plurality of bus lines having upper surfaces parallel to said substrate and inclined sides surfaces and connection portions electrically connected to said bus lines and having upper surfaces parallel to said substrate and inclined surfaces, each of the side surfaces of said bus lines and the side surfaces of said eonduction connection portion are outwardly protruding with respect to a line passing through upper and lower edges of one of the side surfaces; wherein said etching step is carried out so that portions of the side surfaces of said bus lines and the side surfaces of said connection portions are inclined at angles within the range from 20 degrees to 60 degrees with respect to a line parallel to the substrate surface on average with respect to said substrate;

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anodically oxidizing said bus lines and said connection portions so that said bus lines and said connection portions include inner conducting portions and outer insulating oxide films covering said inner conducting portions, respectively.

- 2. The following is an examiner's statement of reasons for allowance: Claims 1, 3-6, 8, 9 and 22-38 are allowed over the prior art of record.
- 3. With regards to claim 1, Zhang in view of Noumi does not teach or fairly suggests, each of the side surfaces of said bus lines and the side surfaces of said connection portion are outwardly protruding with respect to a line passing through upper and lower edges of one of the side surfaces; wherein said etching step is carried out so that portions of the side surfaces of said bus lines and the side surfaces of said connection portions are inclined at angles within the range from 20 degrees to 60 degrees with respect to a line parallel to the substrate surface on average.
- 4. With regards to claim 22, Zhang in view of Noumi, Applicant's Admitted Prior Art and Ghandhi does not teach or fairly suggest washing said substrate, whereby said first oxide film is removed by said washing and said second oxide film is not removed by said washing but remains on said conducting layer so as to cover said conducting layer.
- 5. With respect to claim 31, Zhang in view of Noumi does not disclose or fairly suggest injecting impurities into said semiconductor layer using said gate electrodes including said anodically oxidized film and said insulating film as a mask to form an offset in said semiconductor layer.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue

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fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for

Allowance."

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Fernando L. Toledo whose telephone number is 571-272-1867.

The examiner can normally be reached on Mon-Thu 7am to 5:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Olik Chaudhuri can be reached on 571-272-1855. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

George Fourson

Primary Examiner

Art Unit 2823

FToledo

14 July 2004